



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

10/B

In re application of

Docket No: Q60206

Toshiaki AOAI, et al.

Appln. No.: 09/620,708

Group Art Unit: 1752

Confirmation No.: 3362

Examiner: J. Chu

RECEIVED

AUG 27 2002

TC 1700

Filed: July 20, 2000

For: POSITIVE PHOTORESIST COMPOSITION FOR FAR ULTRAVIOLET  
EXPOSURE

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents  
Washington, D.C. 20231

Sir:

This Amendment is submitted in response to the Office Action dated April 23, 2002. A Petition for a one-month extension of time is being concurrently filed, making a response due on or before August 23, 2002. Please amend the above-identified application as follows:

IN THE CLAIMS:

Please enter the following amended claims:

2 (Amended). The positive photoresist composition as claimed in claim 1, wherein the resin (B) further contains a repeating unit having an alkali-soluble group protected by at least one group containing an alicyclic hydrocarbon structure represented by the following formula (pI), (pII), (pIII), (pIV), (pV) or (pVI):

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